ASMEX.376A PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Todd et al.

Appl. No. : 10/623,482

Filed : July 18, 2003

For : METHOD TO FORM ULTRA

HIGH QUALITY SILICON-CONTAINING COMPOUND

LAYERS

Examiner : Ron Everett Pompey

Group Art Unit : 2812

Supplemental Response

Mail Stop Amendment

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir:

This is a supplemental response to the final Office Action sent electronically on November 27, 2006. Applicants request full consideration of the remarks contained herein.

A Listing of the Claims begins on page 2 of this paper.

Summary of Interview begins on page 4 of this paper.

Remarks/Arguments begin on page 5 of this paper.